

## **SPECIFICATION**

E2100300 -v1

Drawing No Rev. Group

Sheet 1 of 2

### Blank Material, Silicon Test Mass (ETM/ITM), 40m Mariner

Authors	Date	<b>Document Change Notice, Release or Approval</b>	
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#### **Applicable Documents**

LIGO-D20xxxxx-v1 Mirror Blank Drawing, Silicon Test Mass (ETM/ITM), 40m Mariner

Requirements

Physical dimensions Right circular cylinder: 150 mm × 150 mm Ø, per LIGO-D20xxxxx-v1

Clear aperture Central 30 mm diameter

Material Monocrystalline silicon, float zone (Topsil FZ-HiTran or equivalent)

Dopants Undoped; best effort for minimal residual dopant contamination

Resistivity  $> 30 \text{ k}\Omega \text{ cm}$ ; radial variation and striation  $\pm 20\%$  in clear aperture

Interstitial oxygen < 10<sup>16</sup>/cm<sup>3</sup>

Micro defects Voids only; density  $< 10^3/\text{cm}^3$ 

Bubbles/inclusions Total cross section in clear aperture is < 10000 square micrometers

No bubbles > 100 micron diameter; disregard bubbles < 10 micron diameter

Crystal orientation Flat surfaces of cylinder aligned with  $\{100\}$  crystal plane,  $\pm 1^{\circ}$ 

Index homogeneity  $\leq 2.5 \times 10^{-6}$  peak-to-valley;  $\leq 5 \times 10^{-7}$  peak-to-valley in clear aperture

Birefringence  $\leq 5 \text{ nm/cm}$ ;  $\leq 1 \text{ nm/cm}$  in clear aperture

Final shaping Performed using a grit size progression ending with a 320 or smaller grit tool

Defect depth < 0.5 mm on any surface or corner

Serial number Serialized as TMXX, where XX increments starting at 01



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## Blank Material, Silicon Test Mass (ETM/ITM), 40m Mariner

Specification	Method	Inspection Frequency	Data Delivered
Physical dimensions	Inspection	100%	Certification
Material	Process control Material certification	100%	Certification
Dopants	Process control Material certification	100%	Certification
Resistivity	Process control Material certification	100%	Certification
Interstitial oxygen	Process control Material certification	100%	Certification
Micro defects	Process control Material certification	100%	Certification
Bubbles/inclusions	Infrared imaging	100%	Hand sketch indicating location and dimensions
Crystal orientation	Process control Material certification	100%	Certification
Index homogeneity	Interferometric measurement	100%	Inspection report included with certification
Birefringence	Infrared polariscope	100%	Inspection report included with certification
Defect depth	Visual inspection	100%	Certification
Serial number	Visual inspection	100%	Certification

Table 1: MEASUREMENT MATRIX: FREQUENCY AND METHOD